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# MIS Solar Cell Devices based on a Cu<sub>2</sub>O Substrate Utilizing h-BN as an Insulating and Passivating Layer

#### **Supplementary Information**

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#### **Supporting Information Content**

- A) Material Characterization
- B) Photovoltaic Measurement
- C) Electrical Characterization
  - Contact Measurement
  - Capacitance Measurement
  - Quantum Efficiency Measurement
- D) AFM Study

#### A) Material Characterization



Figure S 1 X-ray diffraction pattern of copper foil, partially oxidized and fully oxidized trends.



Figure S 2 Raman spectrum of exfoliated h-BN layer which was transferred to a Si/SiO<sub>2</sub> substrate after Cu<sub>2</sub>O etching. The signature of B-N vibrational  $E_{2g}$  peak of h-BN was observed at 1366.7 cm<sup>-1</sup>. It shows that h-BN remains intact after Cu<sub>2</sub>O growth.

# **B)** Photovoltaic Measurement



Figure S 3 Semi log plot of I-V curve of 3.44% efficient device structure. Voc 0.52V.



**Figure S 4** Measurements of J-V curve of Cu/h-BN/Cu<sub>2</sub>O/CuO/Au-Cr sample with slow and fast voltage sweeping rate of transient (gray curve) and steady state (black curve). Fast sweeping rate between data points improves FF and efficiency. Apparent efficiency calculated over 4% for transient state.

## C) Electrical Characterization

(a)	Carrier Concentration (/cm³)	Mobility (cm²/V·s)	Resistivity (Ω·cm)(300K)
No BN	5.75x10 <sup>17</sup>	15.78	160.257
O <sub>2</sub> Cooling	4.47x10 <sup>18</sup>	34.29	212.716
$N_2$ Cooling	3.45x10 <sup>18</sup>	68.66	102.827
$H_2$ Cooling	8.9x10 <sup>17</sup>	105.73	143.563

Parameters: B=0.6T D=2µm I=0.6mA t=arbitrary



**Figure S 5**a.)Hall effect measurements on Cu<sub>2</sub>O structure formed with introducing different cooling gases b.) Ohmic contact behaviour is shown on IV curve of Au/Cu<sub>2</sub>O/Au Junction.



**Figure S 6** High-frequency (1MHz) C-V curves for Cu<sub>2</sub>O MIS-Schottky cells. Capacitance measurements indicate that h-BN thickness thins down up to 1-2nm by exfoliation process. (Capacitance calculation is made in accumulation state)



**Figure S 7** External quantum efficiency (EQE) spectra of Type 1, Type 2 MIS Schottky solar cells, and Cu/Cu<sub>2</sub>O Schottky solar cell (no h-BN) is shown. The EQE measurements show improvement of incoming photon fraction contribution in the front and rear surfaces of the Type 2 device, while only improvement on the front surface was observed in the Type 1 device. These improvements are based on using the Cu/Cu<sub>2</sub>O Schottky solar cell (no h-BN) as the reference point.

### D) AFM Study



**Figure S 8** AFM study of exfoliated h-BN layer which was transferred to a Si/SiO<sub>2</sub> substrate after Cu<sub>2</sub>O etching. Different data sets from different line scans are shown marked as 1, 2, and 3(green, red, and black respectively), averaged over multiple lines. (Scale-bar: 4 $\mu$ m). h-BN folded at the edge resulting in an initial peak thickness but the AFM study confirms that h-BN thickness is around 1-2nm for the rest of the material.